## **Process Sense™ Endpoint Detector**

**Non-Dispersive Infrared Chamber Clean Endpoint** 



The Process Sense™ endpoint detector is a small, low-cost SiF<sub>4</sub> sensor specifically designed for Remote Plasma Chamber Clean Endpoint detection for silicon-based CVD deposition chambers. Process Sense is based on infrared absorption, the only technique applicable to all plasma cleaning processes (in-situ and remote).

The Process Sense detector gets mounted onto a bypass on the rough line, ensuring no effect on deposition hardware. The signal level reported by the Process Sense detector, which is proportional to  $SiF_4$  concentration, can be used to determine the completion of the chamber clean process.

## **Product Features**

- Sensitivity to SiF<sub>4</sub> down to 1 ppm
- Simple analog output for reported concentration signal

## **Applications**

- Silicon Oxides (USG, FSG, PSG, BSG, BPSG)
- Silicon Nitrides
- Polysilicon
- Silane or TEOS processes

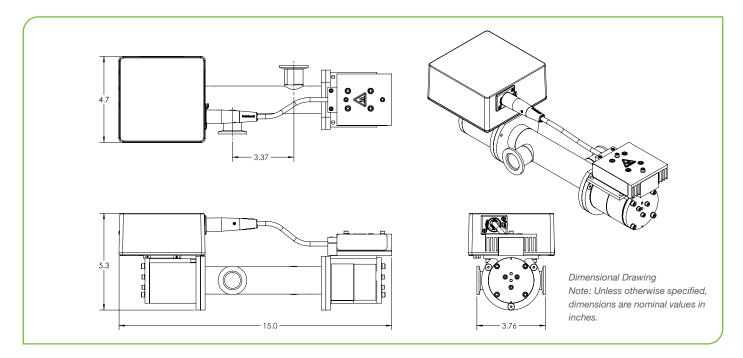


## **Key Benefits**

- Reduced chamber clean times with accurate measurement of SiF<sub>4</sub> concentration
- Accurate determination of chamber clean endpoint reduces chamber wall over etching
- Increase CVD wafer throughput by shortening chamber clean cycle



Specifications	
Measurement Ranges SiF₄ Detection Limit Response Time Calibration Accuracy	1 – 200 ppm (at 760 Torr) 1 ppm SiF <sub>4</sub> (at 760 Torr) 1 second report rate ±10%
Electrical Connector Input Power	DB25 (DB15 adapter available) 24 VDC (2 amp)
Size Dimensions Weight	38 x 12 x 13 cm (15 x 4.5 x 5 in) 2.5 kg (5.5 lbs)
Output Analog 1 (AO1) Analog 2 (AO2) Digital Out	
Sample Conditions Pressure Temperature Hardware Fittings	1 – 760 Torr 25 – 60°C NW25, NW40, NW50 (others available upon request)
Compliance	CE



Please contact your local MKS office for price and availability information.



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